

ABSTRACT OF THE DISCLOSURE

METHOD OF PRODUCING A MODEL FOR ESTIMATING FILM THICKNESS OF
WORKPIECE, METHOD OF ESTIMATING FILM THICKNESS OF WORKPIECE
5 USING SUCH A MODEL, AND COMPUTER-READABLE STORAGE MEDIUM
STORING PROGRAM FOR CAUSING COMPUTER TO PERFORM THE METHODS

A method of producing a model capable of reducing an influence of spectral
variation of reflected light from a workpiece, such as a wafer, and capable of determining an
10 accurate film thickness is disclosed. The method includes: determining sample features
representing features of sample spectra of reflected lights from a sample having a film;
obtaining similarities by calculating a similarity between each of the sample spectra and a
representative spectrum; and producing a film-thickness estimation model by performing
machine learning using training data including the sample features, the similarities, and film
15 thicknesses corresponding to the sample spectra.

FIG. 6